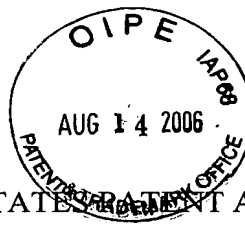


DOCKET NO.: 278426US0PCT



IFW

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

IN RE APPLICATION OF:

GROUP: 3723

Mitsugu ABE, et al.

SERIAL NO: 10/549,294

ATTENTION:

FILING RECEIPT CORRECTIONS

FILED: September 16, 2005

FOR: MATERIAL FOR PURIFICATION OF SEMICONDUCTOR POLISHING
SLURRY, MODULE FOR PURIFICATION OF SEMICONDUCTOR
POLISHING SLURRY AND PROCESS FOR PRODUCING
SEMICONDUCTOR POLISHING SLURRY

2ND REQUEST FOR CORRECTED OFFICIAL FILING RECEIPT

Office of Initial Patent Examination
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

The Patent Office is requested to provide a corrected Official Filing Receipt for the following.

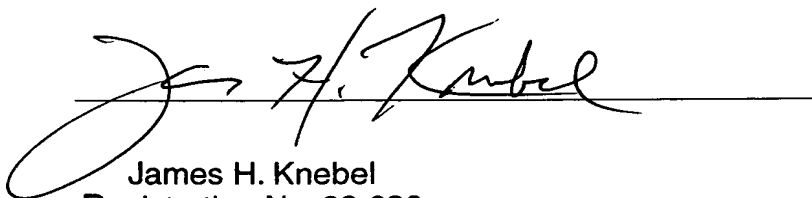
PLEASE NOTE THAT THE 4TH APPLICANT'S CITY IS INCORRECT. IT SHOULD READ AS FOLLOWS:

- 1) MITSUGU ABE, ATSUGI-SHI, JAPAN;
- 2) NOBUYOSHI NAMBU, YOKKAICHI-SHI, JAPAN;
- 3) OSAMU ITO, YOKKAICHI-SHI, JAPAN;
- 4) MASA AKI OGITSU, TSUKUBA-SHI, JAPAN;
- 5) KAZUO INOMATA, TOKYO, JAPAN.

No fees are required. If you have any questions, please do not hesitate to contact us.

Respectfully Submitted,

OBLON, SPIVAK, McCLELLAND,
MAIER & NEUSTADT, P.C.
Norman F. Oblon

A handwritten signature in black ink, appearing to read "J. H. Knebel", is written over a horizontal line.

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DOCKET NO.: 278426US-3069-4314-0PCT
APPLICATION SERIAL NO.: 10/549,294



UNITED STATES PATENT AND TRADEMARK OFFICE

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APPL NO.	FILING OR 371 (c) DATE	ART UNIT	FIL FEE REC'D	ATTY. DOCKET NO	DRAWINGS	TOT CLMS	IND CLMS
10/549,294	09/16/2005	3723	1260	278426US0PCT	6	14	2

CONFIRMATION NO. 8085

22850
C. IRVIN MCCLELLAND
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ALEXANDRIA, VA 22314

REPLACEMENT FILING RECEIPT



OC000000019815891

Date Mailed: 07/31/2006

Receipt is acknowledged of this regular Patent Application. It will be considered in its order and you will be notified as to the results of the examination. Be sure to provide the U.S. APPLICATION NUMBER, FILING DATE, NAME OF APPLICANT, and TITLE OF INVENTION when inquiring about this application. Fees transmitted by check or draft are subject to collection. Please verify the accuracy of the data presented on this receipt. **If an error is noted on this Filing Receipt, please mail to the Commissioner for Patents P.O. Box 1450 Alexandria Va 22313-1450. Please provide a copy of this Filing Receipt with the changes noted thereon. If you received a "Notice to File Missing Parts" for this application, please submit any corrections to this Filing Receipt with your reply to the Notice. When the USPTO processes the reply to the Notice, the USPTO will generate another Filing Receipt incorporating the requested corrections (if appropriate).**

Applicant(s)

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TSUKUBA-SHI

Assignment For Published Patent Application

Nomura Micro Science Co., Ltd., Atsugi-shi, Kanagawa, JAPAN

RECEIVED: 8/1/06
OBLON, SPIVAK, McCLELLAND
MAIER & NEUSTADT, P.C.

DOCKETING DEPT

Initials/Date Docketed: 8/1/06

Type of Resp(s):

Due Date(s):

Power of Attorney: The patent practitioners associated with Customer Number 22850.

Domestic Priority data as claimed by applicant

This application is a 371 of PCT/JP04/03642 03/18/2004

Foreign Applications

JAPAN 2003-074581 03/18/2003

If Required, Foreign Filing License Granted: 06/04/2006

The country code and number of your priority application, to be used for filing abroad under the Paris Convention, is **US10/549,294**.

Projected Publication Date: 09/14/2006

Non-Publication Request: No

Early Publication Request: No

Title

Material for purification of semiconductor polishing slurry, module for purification of semiconductor polishing slurry and process for producing semiconductor polishing slurry

Preliminary Class

451

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